

Oxidation of ZrB_2 SiC TaSi₂ Materials at Ultra High Temperatures

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ZrB_2 - 20v% SiC - 20v% TaSi₂ was oxidized in stagnant air for ten minute cycles for times up to 100 minutes at 1627°C and 1927°C. The sample oxidized at 1627°C showed oxidation resistance better than that of the standard ZrB_2 - 20v% SiC. The sample oxidized at 1927°C, however, showed evidence of liquid phase formation and complex oxidation products. The sample exposed at 1927°C was analyzed in detail by scanning electron microprobe and wavelength dispersive spectroscopy to understand the complex oxidation and melting reactions occurring during exposure. The as hot-pressed material shows the formation of a $Zr(Ta)B_2$ phase in addition to the three phases in the nominal composition already noted. After oxidation, the TaSi₂ in the matrix was completely reacted to form Ta(Zr)C. The layered oxidation products included SiO₂, ZrO₂, Ta₂O₅, and a complex oxide containing both Zr and Ta. Likely reactions are proposed based on thermodynamic phase stability and phase morphology.



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Background

- Previous work

"Oxidation of ZrB_2 - and HfB_2 -based ultra-high temperature ceramics: effect of Ta additions," E. Opila, S. Levine, J. Lorincz, J. Mat. Sci. 39 [19] 5969-5977 (2004).

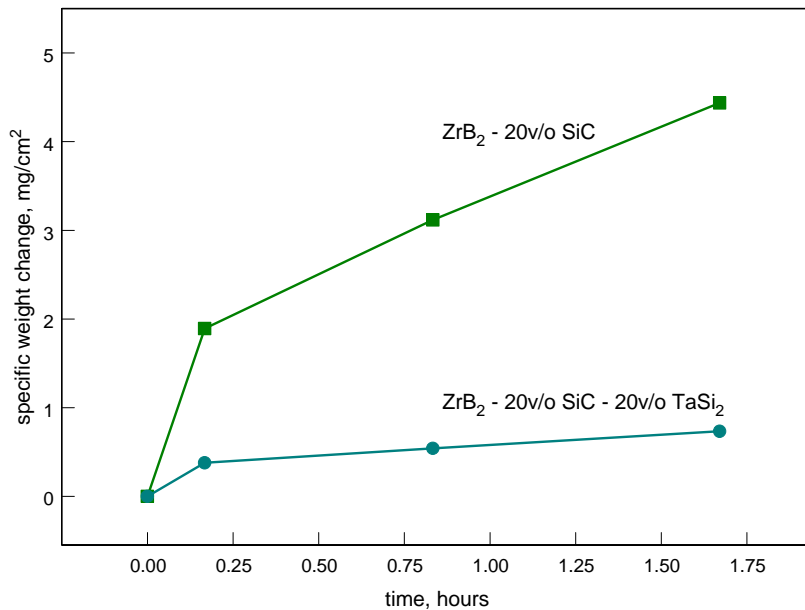
- Improved oxidation resistance with 20 v/o $TaSi_2$ additions to ZrB_2 - 20 v/o SiC at $1627^\circ C$ in air up to 100 minutes
- Improved oxidation resistance attributed to Ta additions, not excess Si
- Oxidation at $1927^\circ C$ resulted in excess liquid phase formation and poor oxidation resistance

ZrB₂ - 20v/o SiC - 20v/o TaSi₂ showed improved oxidation resistance at 1627°C in air

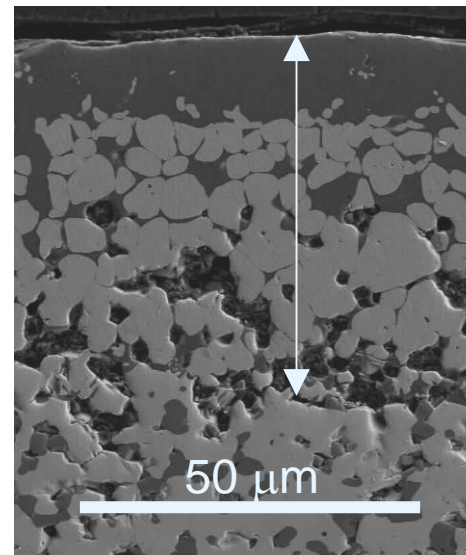
ZS: 1, 5, and 10 cycles



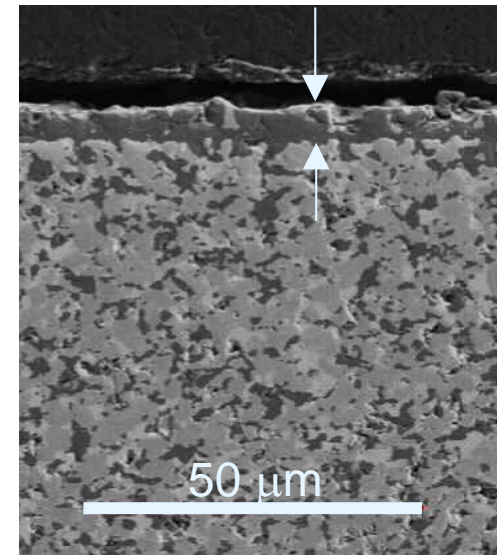
ZS20TS: 1, 5, and 10 cycles



oxidized in 10 minute cycles

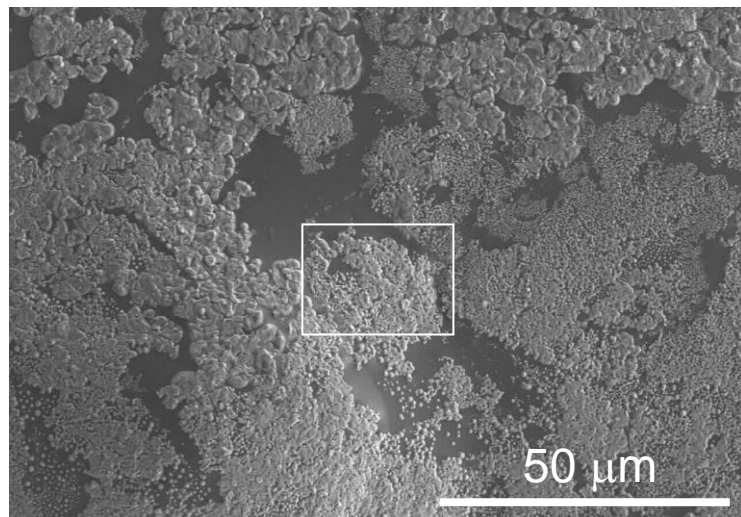


ZrB₂ - 20v/o SiC

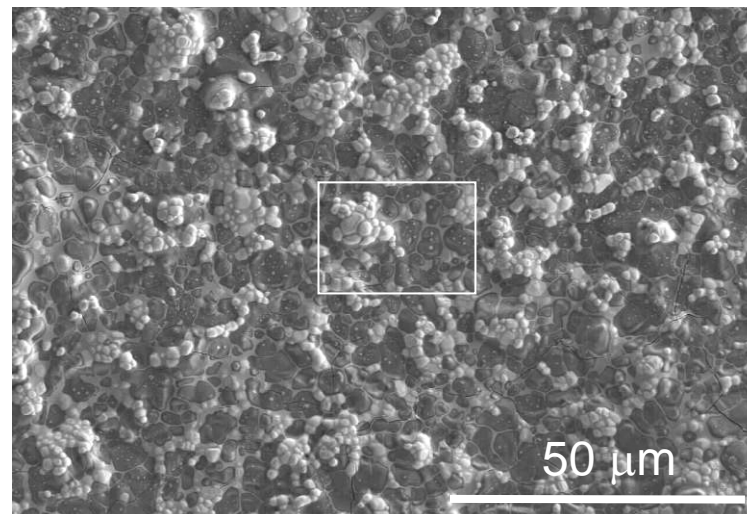


ZrB₂ - 20v/o SiC -
20v/o TaSi₂

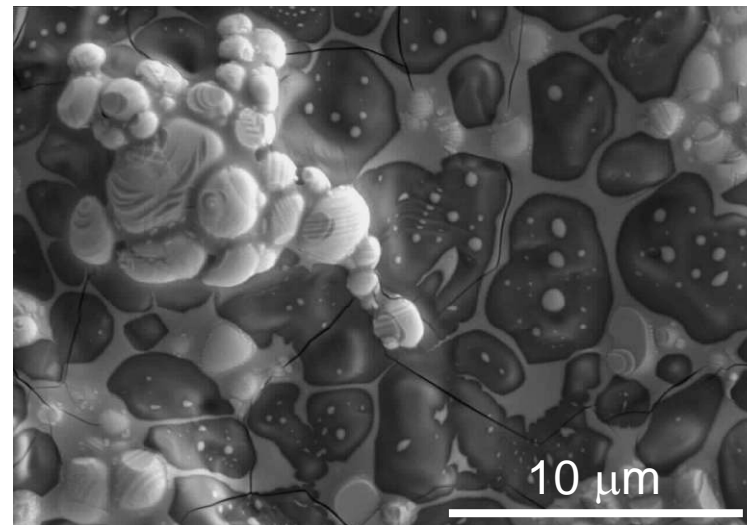
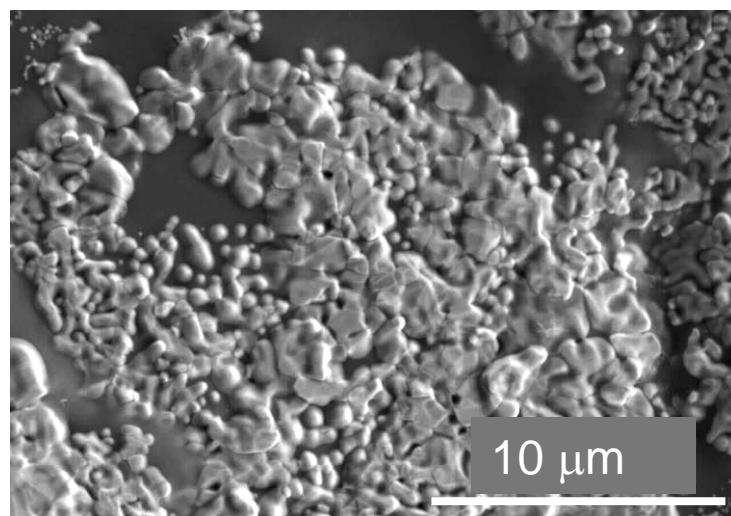
Surface oxide morphology, 1627°C, 100 min, air



ZS



ZS20TS



Melt formation observed after ZS20TS oxidation at 1927°C in stagnant air



ZSTs: as-fabricated
and 1 cycle



ZSTs: 5 cycles



Liquid phase formation a problem

- SiO_2 : $T_m = 1723^\circ\text{C}$
- Ta_2O_5 : $T_m = 1887^\circ\text{C}$
- $\text{Ta}_2\text{O}_5 \cdot 6\text{ZrO}_2$: $T_m > 1870^\circ\text{C}$

ZrO_2 provides some dimensional stability



ZS: 1, 5, and 10 cycles



Questions arising from 1927°C exposure

- Ta distribution in oxidation products
 - is all Ta contributing to melt formation?
 - any Ta in solid phases?
- What is the composition of oxidation products?
- Can liquid phase formation be limited while still retaining improved oxidation resistance at 1627°C?

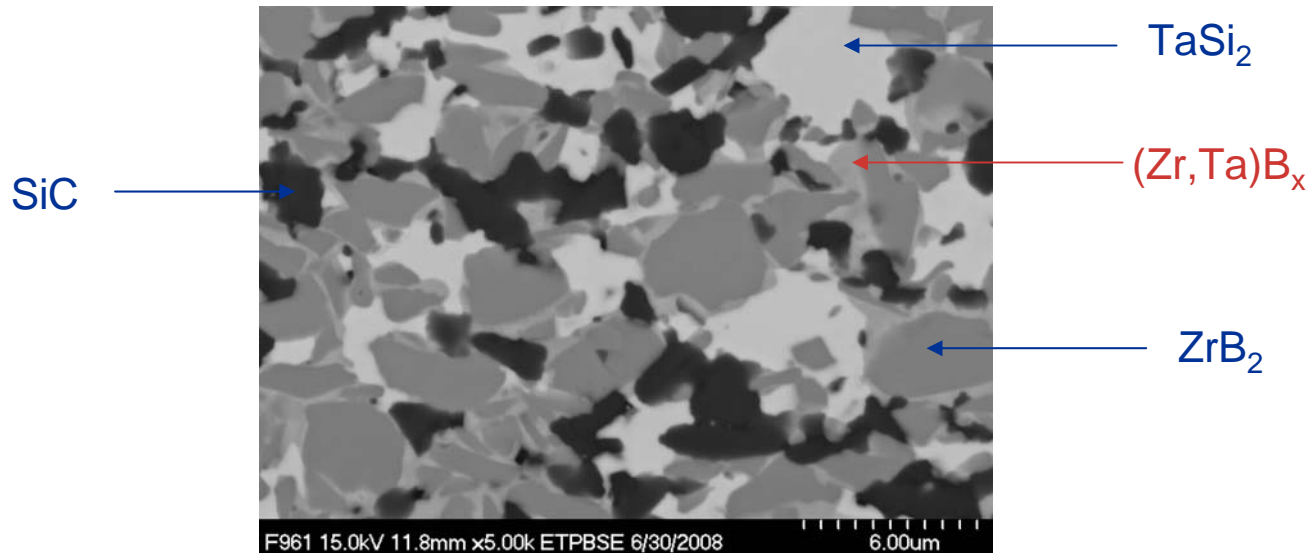


Additional work since previous publication

- Characterization of ZS20TS after 1927°C, 5 x 10 min cycles in stagnant air
 - WDS/microprobe: JEOL 8200
 - FE-SEM: Hitachi S-4700
- Oxidation of ZS5TS at 1627°C, 1927°C for 1, 5 and 10 ten-minute cycles in stagnant air

Characterization of ZS20TS **starting material**

- Desired composition: ZrB_2 - 20v% SiC - 20v% TaSi_2
- As hot-pressed material shows 4 phases
 - Phase 1: ZrB_2 B/Zr = 1.97
 - Phase 2: SiC C/Si = 1.08
 - Phase 3: TaSi_2 Si/Ta = 2.16
 - Phase 4: $(\text{Zr,Ta})\text{B}_x$ Zr/Ta = 4.19 B/(Zr+Ta) = 1.53





Stability of TaSi₂

ΔG_f 1927°C(kJ/mol) $M+X_x=MX_x$

TaSi₂ -61

TaC -140

TaB₂ -191

TaO_{2.5} -615

ZrSi₂ -141

ZrC -180

ZrB₂ -285

ZrO₂ -741

- Silicides are least stable
- Zirconium compounds are more stable than tantalum compounds
- (Zr,Ta)B_x formation: TaSi₂ reacts with excess B during hot pressing?

ZrB₂ TaB₂ solid solution?

- ZrB₂ and TaB₂ both hexagonal crystal structure
- Limited phase stability info found

Leitnaker, Bowman, Gilles,
J. Electrochem. Soc. 109 [5] 441 (1962).

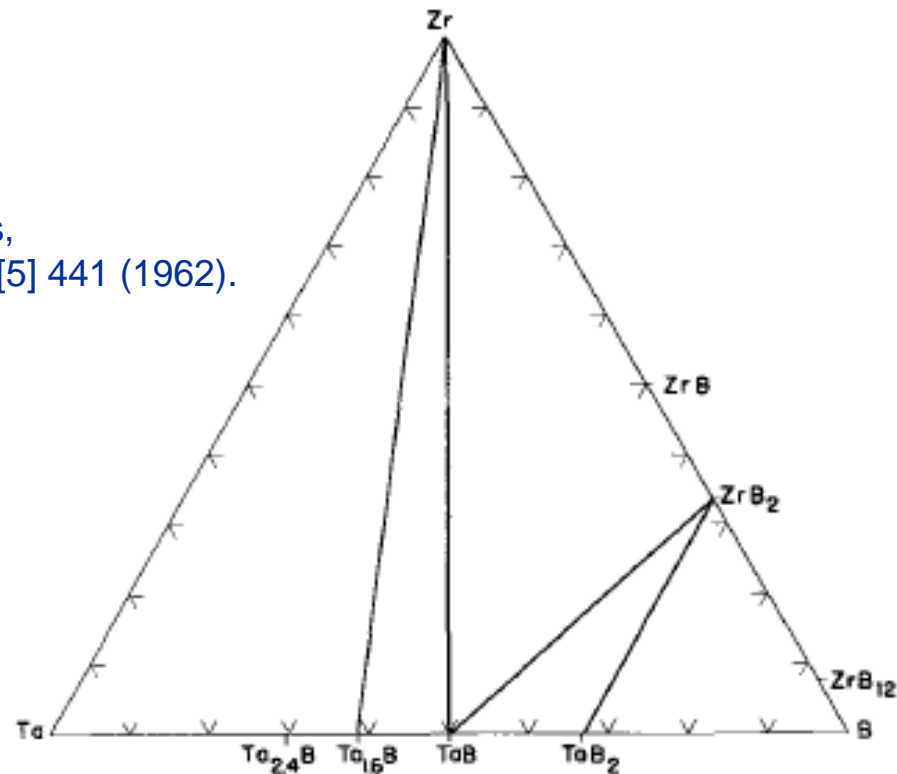


Fig. 1. Schematic phase diagram for the Ta-Zr-B system for a temperature of 1500°C.

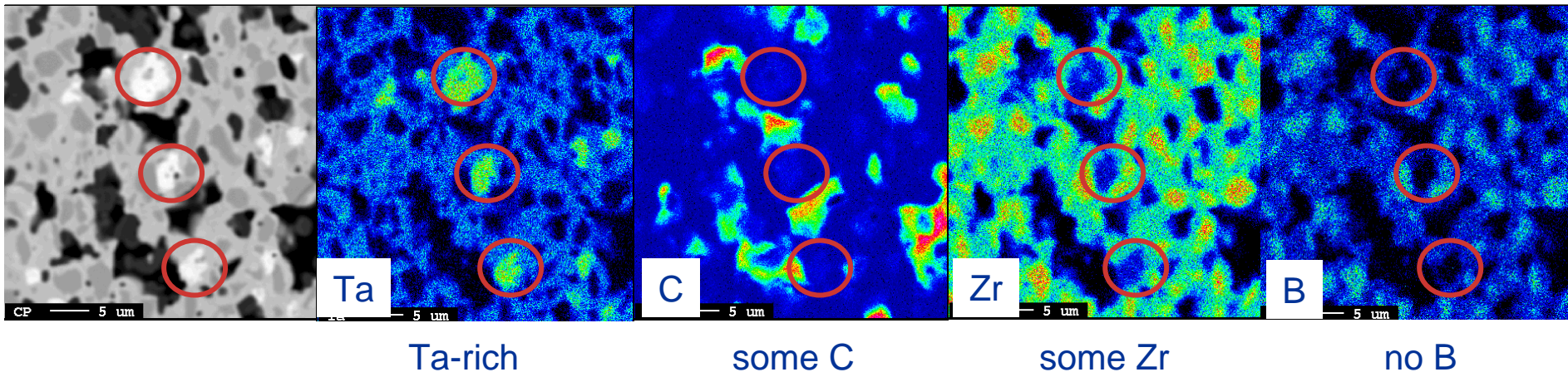


Characterization of ZS20TS after 1927°C oxidation

- Extensive melt formation
- Characterizing phase formation after cooling
- Not necessarily equilibrium phase formation

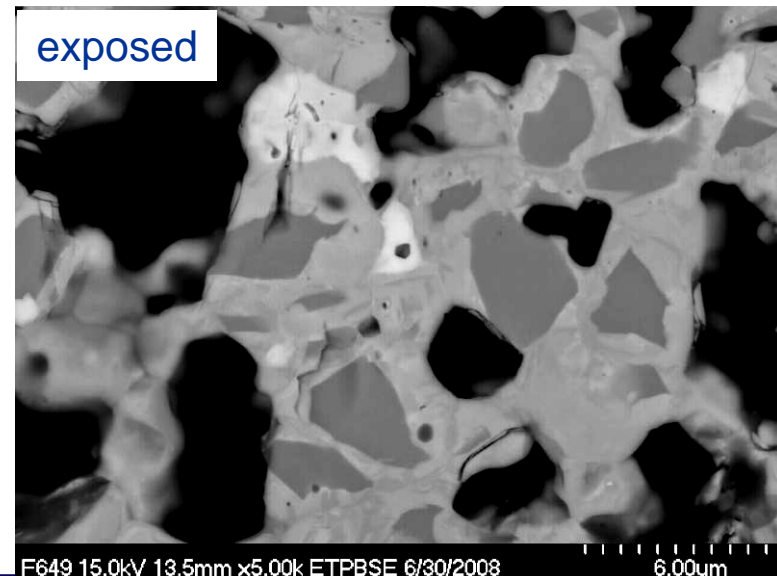
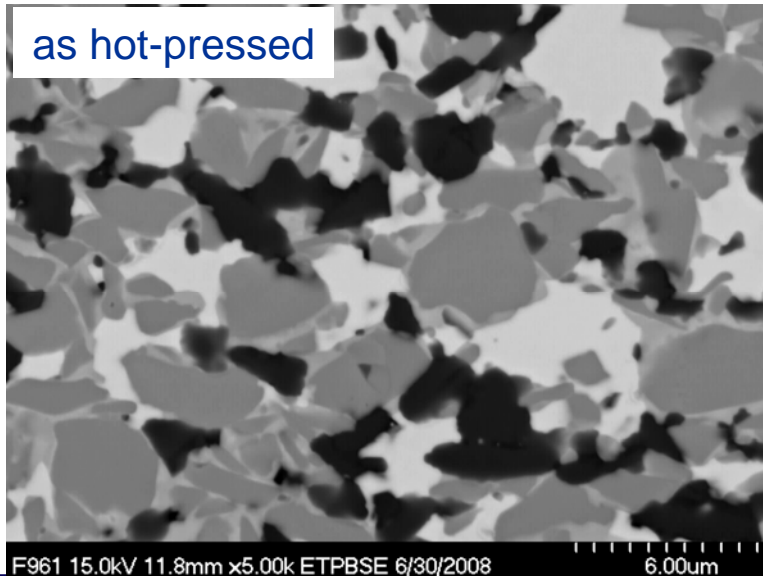
Characterization of ZSTS(20) after oxidation at 1927°C: matrix phases

- TaSi₂ is gone. $T_m \text{ TaSi}_2 = 2200^\circ\text{C}$ (HSC, Kosolapova)
- Four phases observed:
 - Phase 1: ZrB₂ B/Zr = 1.98
 - Phase 2: SiC C/Si = 1.05
 - Phase 3: (Zr,Ta)B_x Zr/Ta = 3.47 B/(Zr+Ta) = 1.43
 - Phase 4: (Zr,Ta)C_x Zr/Ta = 0.56 C/(Zr+Ta) = 1.42



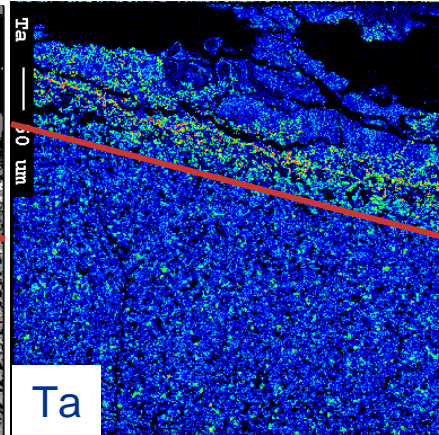
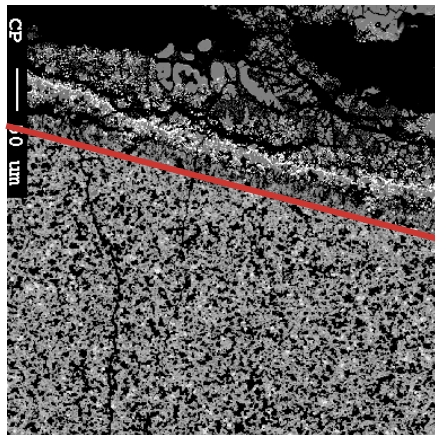
Evolution of matrix after oxidation

- Loss of TaSi_2 , appearance of TaC
 - Active oxidation of TaSi_2 leaving Ta?
 - TaC more stable than SiC
 - $\text{TaSi}_2 + \text{SiC} + 1.5 \text{O}_2(\text{g}) = \text{TaC} + \text{SiO}(\text{g}) \quad \Delta G_{\text{rxn}} = -79 \text{kJ/mol}$
- Change in phase distribution
 - Decrease of ZrB_2 , SiC
 - (Increase of $\text{Zr, Ta})\text{B}_x$

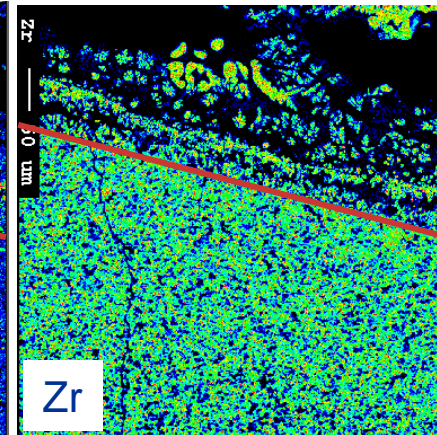


General characteristics of oxide layers

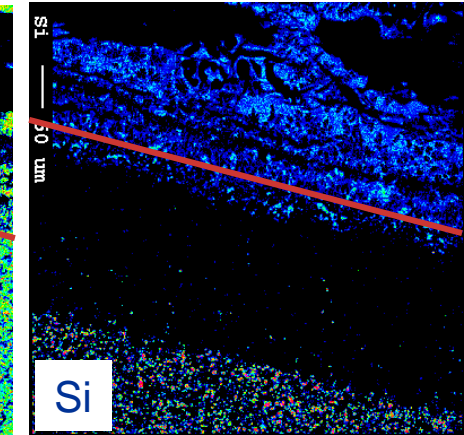
ZS20TS 1927°C 50 minutes air



Ta concentrated near initial interface, but present throughout scale

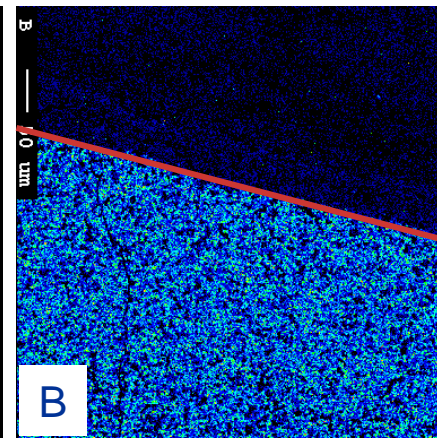
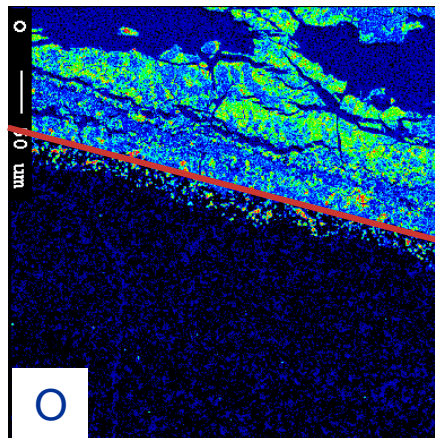


Zr forms discrete oxide particles



Silica is present in most of scale, Si depletion layer below oxide

Oxides found below interface, silica?



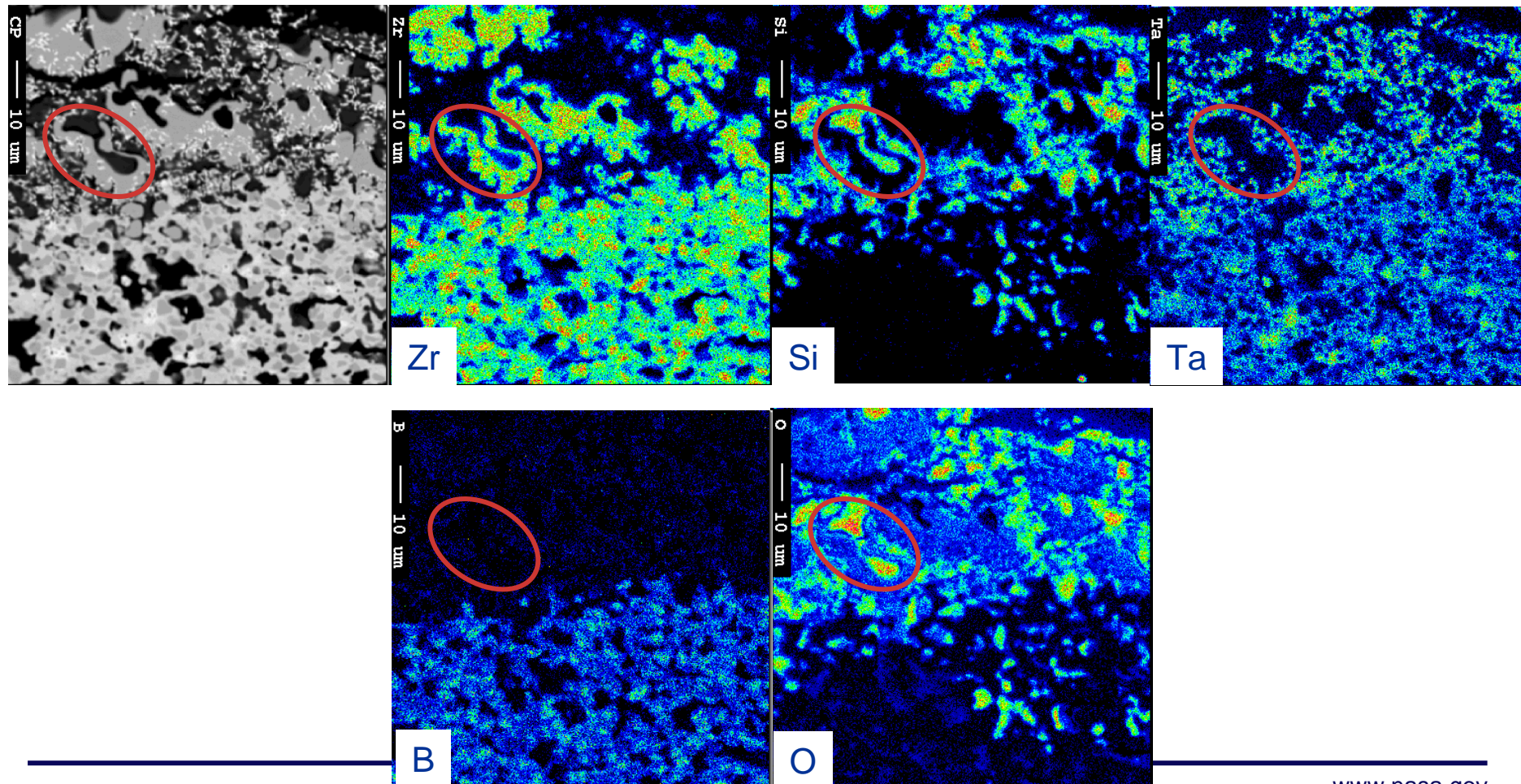
ZrB₂ and SiO₂ coexist in layer below interface. Some B in near surface oxide layer?

Characterization of ZS20TS after oxidation at 1927°C: oxide phases adjacent to matrix

ZrO₂ O/Zr = 1.96

SiO₂ O/Si = 1.96

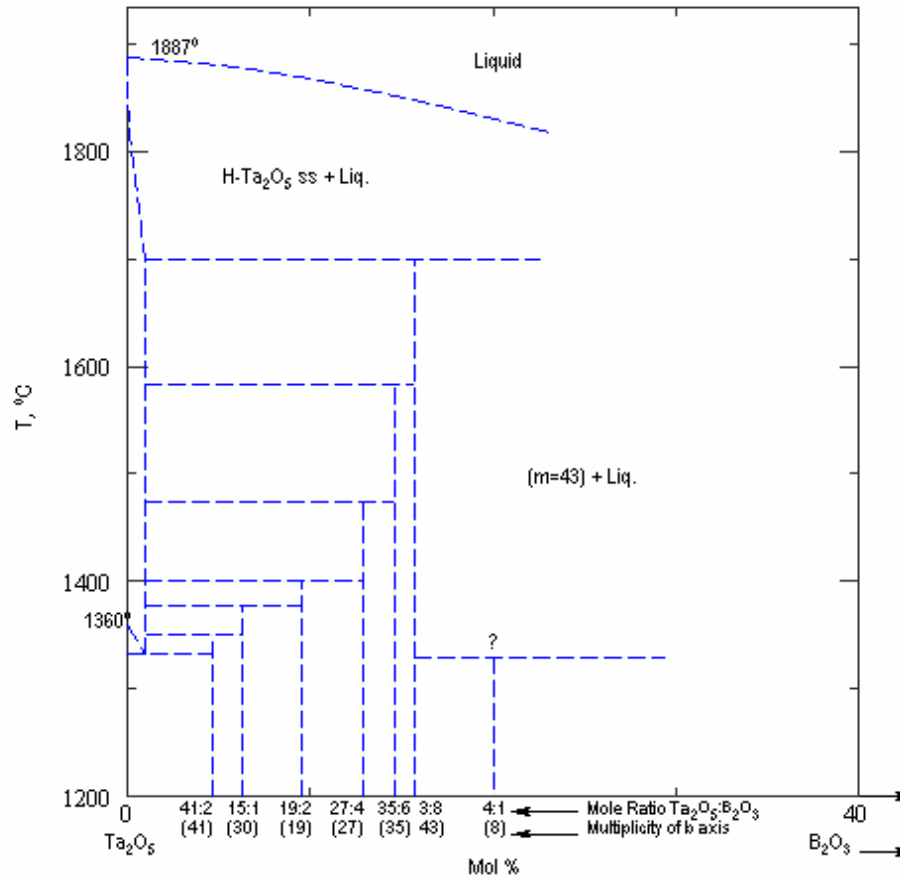
Ta(Zr)B(O) Ta/Zr = 7.49 B/O = 2.16 (B+O)/(Ta+Zr) = 1.36, not Ta₂O₅





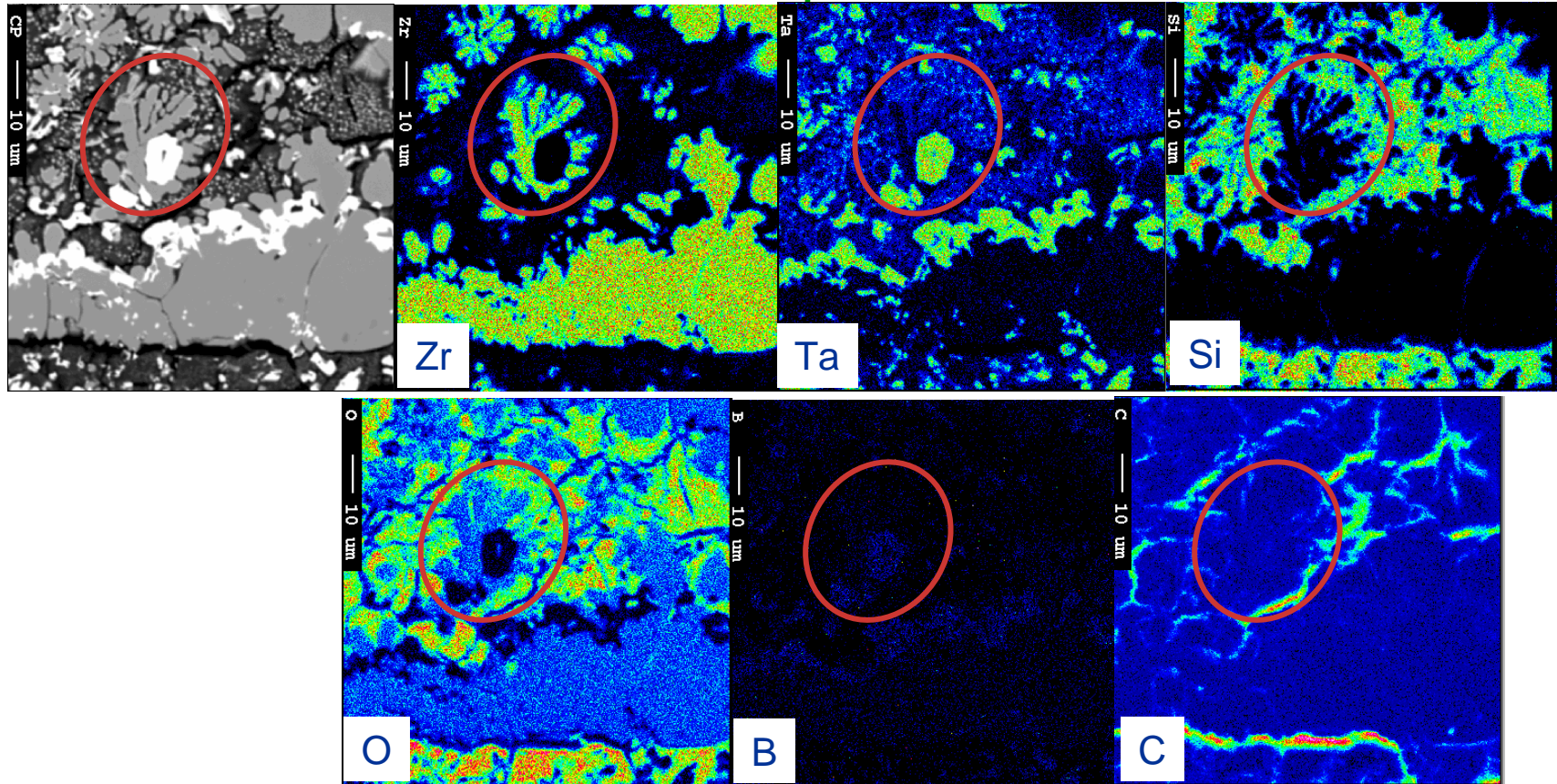
(Ta,Zr)(B,O)?

- TaB₂ sampling ZrO₂ underneath small Ta-rich particles?
- Ta oxyboride?
 - Oxynitrides and oxycarbides known to exist
 - Ta O B phase diagram



Phase Diagrams for Ceramists
Diagram 4392
RS Roth, JL Waring, 1970.

Characterization of ZS20TS after oxidation at 1927°C: middle portion of scale



ZrO₂ large continuous regions O/Zr = 1.98

SiO₂ O/Si = 2.39? some Ta 1.6at%

Ta(B,O) B/O = 1.71 (O+B)/Ta = 0.73 phase separated in silica

Ta(C,B) not expected: C/B = 1.34 (C+B+O)/Ta = 1.00

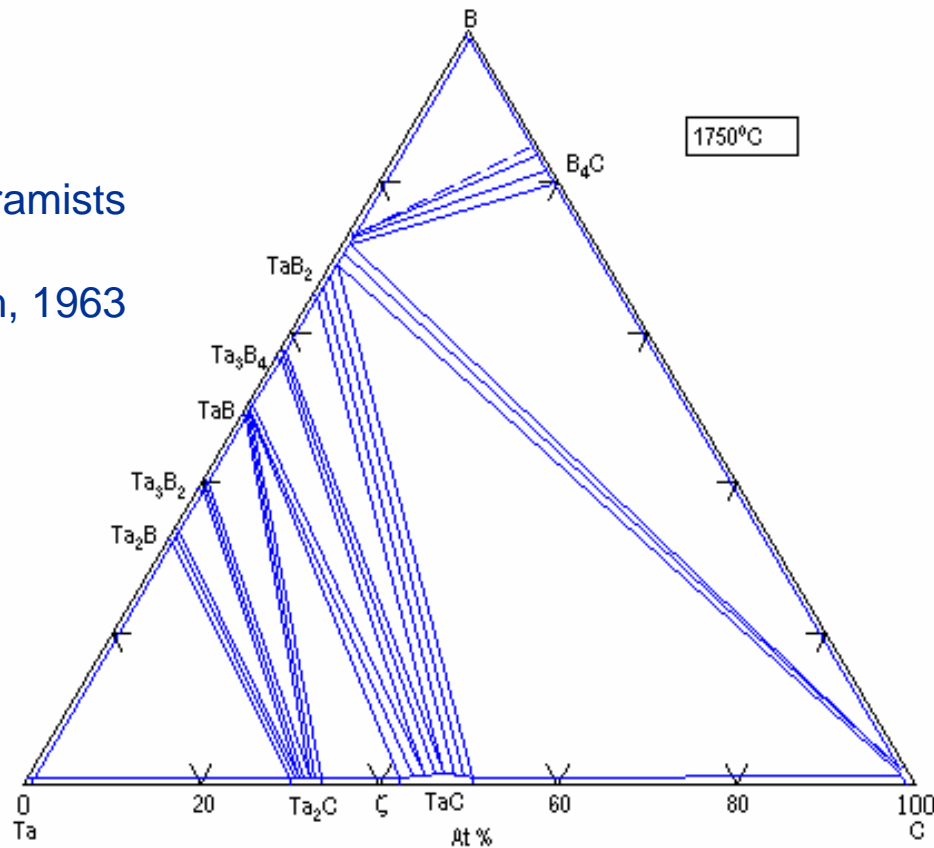
Additional phase not analyzed by microprobe



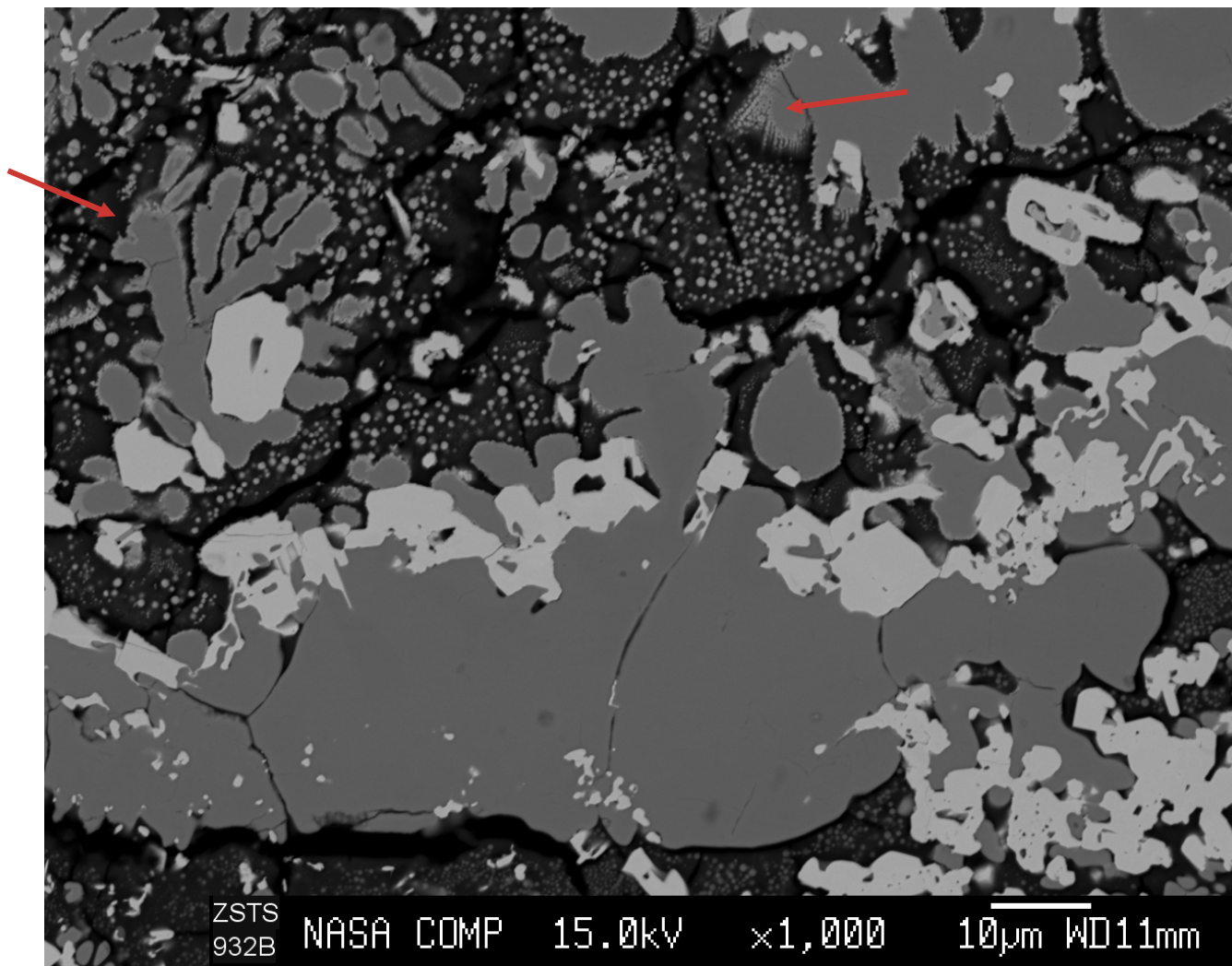
Ta(C,B)?

- TaC and TaB₂ both significantly less stable than oxide phase
 - ZrO₂ more stable than Ta₂O₅ (Ellingham diagram)
- Unexpected phase formation: TaC cubic, TaB₂ hexagonal
 - Artifact of sampling volume?

Phase Diagrams for Ceramists
Diagram 8865
Rudy, Benesovsky, Toth, 1963



TaZrO phase morphology on ZrO_2 suggests surface reaction, Phase V?



Characterization of ZSTS(20) after oxidation at 1927°C: loose outer portion of scale

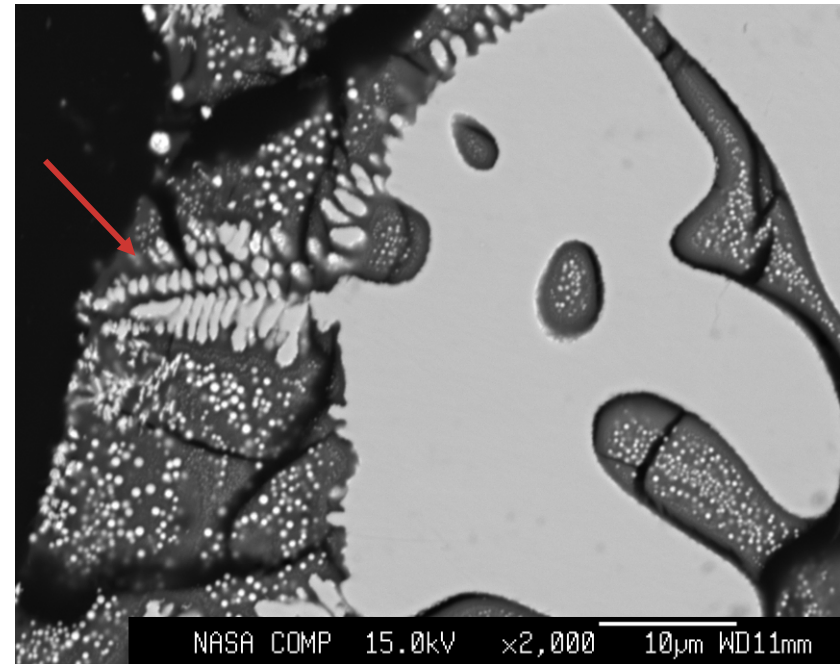
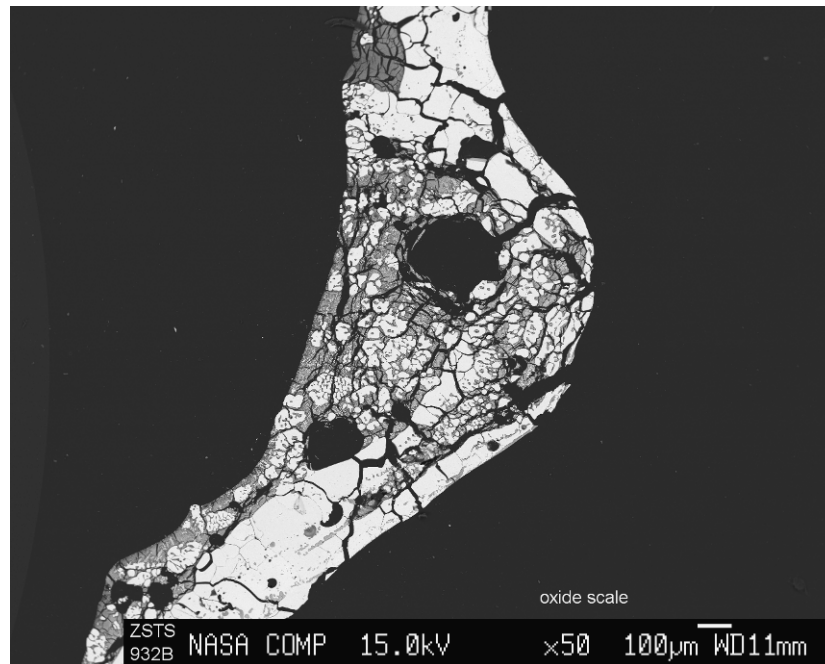
ZrO₂ O/Zr = 2.07 dendrites observed

SiO₂(Ta) O/(Si+Ta) = 2.917

(Zr,Ta)O phase separated in silica

Zr/Ta = 1.92, not Phase V, Zr/Ta= 5.5 to 6

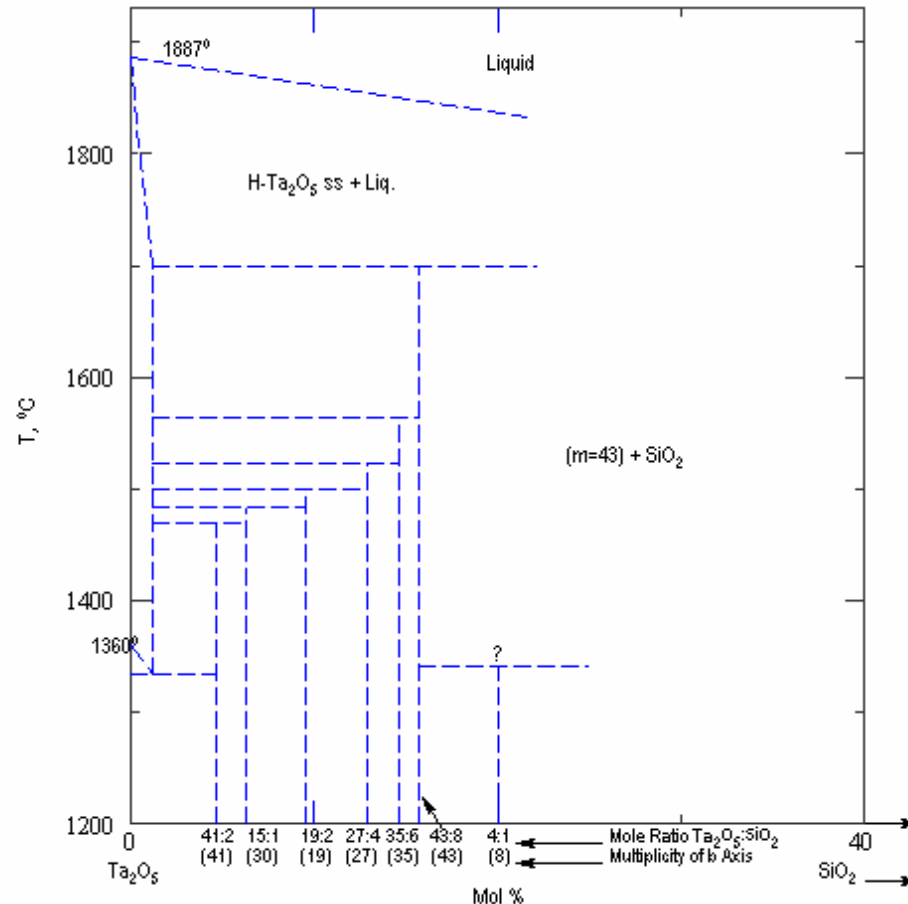
O/(Zr+Ta) = 2.47, expected ratio for Ta₂O₅





Ta Si O

- WDS results suggest Ta-O in solution with SiO_2
- Available phase diagram suggests ordering is possible



Phase Diagrams for Ceramists
Diagram 4448
RS Roth, JL Waring, 1970.



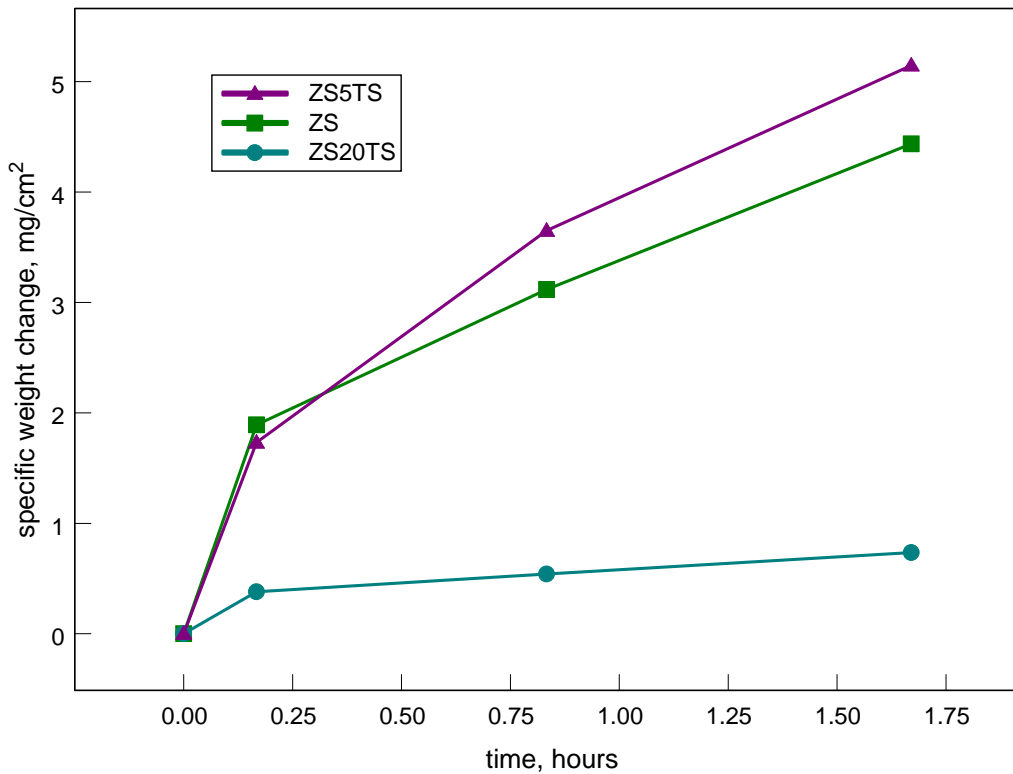
Summary of observations for ZSTS(20) oxidation at 1927C

- Zr- and Ta-borides form solid solution
- TaSi_2 is not stable after exposure at 1927°C , about $300^\circ\text{C} < T_m$
- Possible active oxidation of TaSi_2 resulting in $\text{SiO}(\text{g})$ and TaC formation
- Oxidation microstructure is fine near matrix interface, coarse at outer surface
- $\text{Ta}(\text{C},\text{B})$ appears to remain unoxidized amidst ZrO_2 scale
- Unexpected formation of $\text{Ta}(\text{C},\text{B})$ in scale?
- Melt formation: ZrO_2 SiO_2 Ta_2O_5 all in solution
 - $\text{Ta}(\text{B},\text{O})$ phase separated in silica rich areas
 - $\text{Si}(\text{Ta})\text{O}$
 - Dendritic structure of Phase V (?) on surface of ZrO_2 , $\text{Ta}(\text{C},\text{B})$
 - Dendritic structure of ZrO_2 in outer scale



Optimization of TaSi₂ additions

Oxidation of ZS5TS at 1627°C in air



ZS20TS: 1, 5, and 10 cycles



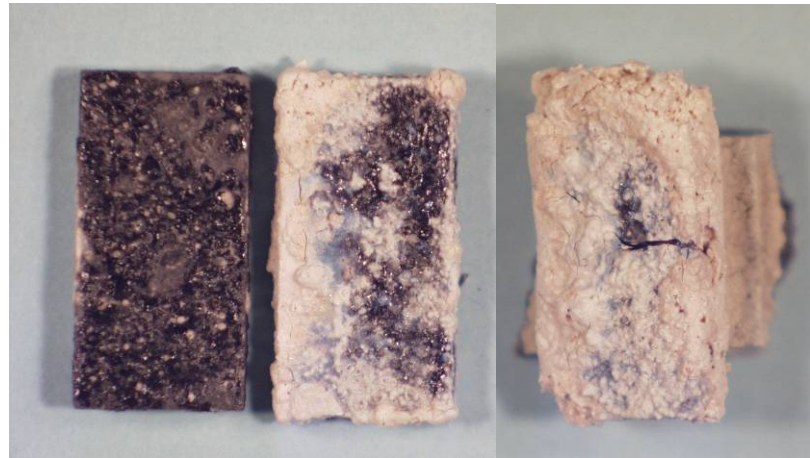
ZS5TS: 1, 5, and 10 cycles



ZS: 1, 5, and 10 cycles



Oxidation: 10 minute cycles at 1927°C in stagnant air



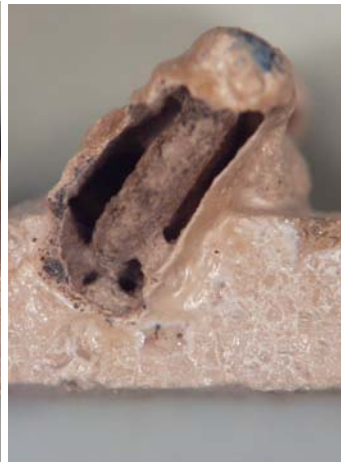
ZS5TS: 1, 5, and 7 cycles



ZS20TS: 1 cycle



ZS20TS: 5 cycles



ZS: 1, 5, and 10 cycles



Summary of oxidation results for ZS5TS

- 5 volume % addition of TaSi_2 to ZS is not enough to promote improved oxidation behavior at 1627°C
 - Oxidation weight gain and appearance similar to ZS (no TaSi_2 additions)
- 5 volume % addition of TaSi_2 to ZS still results in extensive melt formation and undesirable scale morphology during oxidation at 1927°C
- Oxidation behavior of ZS can not be improved at both 1627°C and 1927°C with TaSi_2 additions



Conclusions: $\text{ZrB}_2\text{-SiC-TaSi}_2$

- 20 v% TaSi_2 additions to ZrB_2 - SiC result in formation of phase separated glass and improved oxidation resistance at 1627°C
- At 1927°C excessive melt formation prevents dimensional stability of oxides formed from ZrB_2 - SiC - TaSi_2
- TaSi_2 reacts to form $(\text{Zr,Ta})\text{B}_x$, $\text{Ta}(\text{C,B})$ as well as melt solution phases containing Ta, Zr, Si, O, B
- TaSi_2 additions can not be optimized to form both phase separated glass at 1627°C and oxides with dimensional stability at 1927°C .
- More phase stability work needed in UHTC systems



Acknowledgments

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